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- **Ota, Hirohisa**
Tokyo (JP)
- **Nakamura, Takashi**
Tokyo (JP)
- **Kasumi, Kazuyuki**
Tokyo (JP)
- **Tokita, Toshinobu**
Tokyo (JP)

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(71) Applicant: **CANON KABUSHIKI KAISHA**
Ohta-ku, Tokyo (JP)

(72) Inventors:

- **Kawakami, Eigo**
Tokyo (JP)

(74) Representative: **Weser, Wolfgang**
Weser & Kollegen,
Patentanwälte,
Radeckestrasse 43
81245 München (DE)

(54) **Apparatus and method for transferring a pattern**

(57) A processing apparatus for transferring a relief pattern on a mold to a resist on a substrate through a compression of the mold against the resist, and an irradiation of light for exposing the resist onto the resist includes a mold chuck for holding the mold and for compressing the mold against the resist, and a deformation reducing part for reducing a deformation of the mold when the mold chuck applies a compression force to the mold.

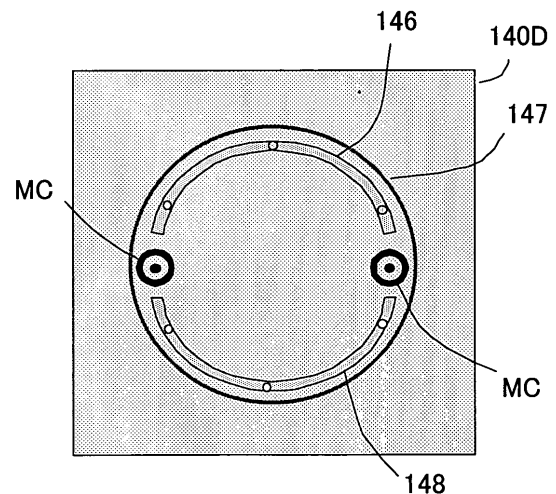


FIG. 10A

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